

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	4052	resist same "lift off"	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 09:50
L6	169	(resist or photoresist) and "lift off" and "hydrogen peroxide" and solvent	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 10:28
L7	1271	(resist or photoresist) and remov\$3 and spray\$4 and "hydrogen peroxide" and solvent	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 10:33
L10	448	(resist or photoresist) and remov\$3 and spray\$4 and "hydrogen peroxide" and solvent and (polymer or "low K") and (Cu or copper)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 11:15
L11	215	(resist or photoresist) and remov\$3 and spray\$4 and "hydrogen peroxide" and solvent and (polymer or "low K") and (Cu or copper) and rins\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 10:41
L12	58	(resist or photoresist) and remov\$3 and spray\$4 and "hydrogen peroxide" and solvent and (polymer or "low K") and (Cu or copper) and (recycl\$4 or recirculat\$4)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 11:16
L13	130	(resist or photoresist) and remov\$3 and spray\$4 and "hydrogen peroxide" and solvent and (polymer or "low K") and (Cu or copper) and rotat\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 11:17
L14	475	(resist or photoresist) and remov\$3 and spray\$4 and "hydrogen peroxide" and (solvent or amine) and (polymer or "low K") and (Cu or copper)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 11:18
L15	0	"475" and 438/4ccls.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 11:18
L16	35	14 and "438"/\$.ccls.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/06 11:19
L17	3009	((134/1.1) or (134/1.2) or (134/1.3) or (134/2)).CCLS.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/06 11:20

L18	75	17 and 7	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/06 11:20
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